WHAT IS CLAIMED IS:

1. A substrate treating apparatus comprising:

a plasma generating part configured to generate plasma;

a housing disposed under the plasma generating part, and having a space therein;

a susceptor disposed within the housing and supporting a substrate; and

a baffle comprising injection holes injecting the plasma supplied from the plasma generating part, to the substrate,

wherein the baffle comprises a base in which the injection holes are formed, ~~and~~

a central portion of the base is thicker than an edge thereof, and a coupling part having a ring shape and protruding upward from an edge of the top surface of the base, and an upper end of the coupling part is higher than a central portion of the top surface of the base.

2. The substrate treating apparatus of claim 1, further comprising a sealing cover that seals an open top of the housing, and comprises an introduction port through which plasma is introduced from the plasma generating part,

wherein the central portion of the base faces the introduction port.

3. The substrate treating apparatus according to one of claim 1 to 2, wherein the base gradually decreases in thickness from the central portion thereof to the edge thereof.

4. The substrate treating apparatus according to one of claim 1 to 3, wherein the base has a curved top surface protruding upward, and a flat bottom surface.

5. The substrate treating apparatus according to one of claim 1 to 3, wherein the base has a curved top surface protruding upward, and a curved bottom surface protruding downward.

6. The substrate treating apparatus according to ~~of any~~ one of claims 1 to 5, wherein the injection holes comprise:

a plurality of first injection holes disposed in the central portion of the base; and

a plurality of second injection holes disposed in the edge of the base, and having radii greater than those of the first injection holes.

7. The substrate treating apparatus of claim 6, wherein a distance between the second injection holes is greater than a distance between the first injection holes.

~~8. The substrate treating apparatus of any one of claims 1 to 5, wherein the baffle further comprises a coupling part having a ring shape and protruding upward from a edge of the top surface of the base, and~~

~~an upper end of the coupling part is higher than a central portion of the top surface of the base.~~

8~~9~~. The substrate treating apparatus according to one of claim 1 to 7~~8~~, wherein the baffle further comprises a rib part protruding from the upper end of the coupling part toward the central portion of the base, and spaced apart from the top surface of the base.

9~~10~~. The substrate treating apparatus of claim 8~~9~~, wherein a connecting region between a bottom surface of the rib part and an inner surface of the coupling part, and a connecting region between the inner surface of the coupling part and the top surface of the base are rounded.

10~~11~~. The substrate treating apparatus according to one of claim 1 to 9~~8~~, wherein an exhausting hole is disposed in a connecting region between the edge of the base and the coupling part, and is a through hole downwardly and obliquely extending from an inner surface of the coupling part to an outer surface thereof.

1112. The substrate treating apparatus of claim 109, wherein the exhausting hole is provided in plurality, and the exhausting holes are spaced apart from each other along the coupling part, and have slit shapes.

1213. A baffle comprising:

a plurality of injection holes configured to inject plasma; and

a base in which the injection holes are formed,

wherein a central portion of the base is thicker than an edge thereof; and

a coupling part that has a ring shape and protrudes upward from an edge of the top surface of the base, and

wherein an upper end of the coupling part is higher than a central portion of the top surface of the base.

1314. The baffle of claim 1213, wherein the base has a curved top surface protruding upward, and a flat bottom surface.

1415. The baffle of claim 1213, wherein the base has a curved top surface protruding upward, and a curved bottom surface protruding downward.

~~16. The baffle of any one of claims 13 to 15, further comprising a coupling part that has a ring shape and protrudes upward from a edge of the top surface of the base, and~~

~~wherein an upper end of the coupling part is higher than a central portion of the top surface of the base.~~

15~~17~~. The baffle according to one of claim 12 to 14~~16~~, further comprising a rib part that protrudes from the upper end of the coupling part toward the central portion of the base, and is spaced apart from the top surface of the base.

16~~18~~. The baffle according to one of claim 12 to 15~~16~~, further comprising exhausting holes that are disposed in a connecting region between the edge of the base and the coupling part, that are spaced apart from each other along the coupling part, and that are through holes downwardly and obliquely extending from an inner surface of the coupling part to an outer surface thereof.